



SHEET 1 OF 1

FORM PTO-1449		DOCKET NUMBER WSC 303		APPLICATION NUMBER 10/760,661		
INFORMATION DISCLOSURE CITATION IN AN APPLICATION		APPLICANT(S) Mark L. Jones et al.				
		FILING DATE January 15, 2004		GROUP ART UNIT 1743		
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
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/B.R./	C.M. McCarthy et al., <i>Room Temperature Copper Out-Diffusion from the Bulk of Silicon Wafers and its Behavior Following Various Postanneal Treatments</i> , ECS Proc. 98-1, 629-640 (1998)					
EXAMINER /Bobby Ramdhanie/ (08/14/2007)			DATE CONSIDERED 08/14/2007			